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•E	*Examiner Initial			Document Number	Date		Namê		Class	Sub- class		Filing Date If Appropriate		
	6			6,503,818 B1	01-2003	Jar	ıg		_					
П	AB			6,486,061 B1	11-2002	Xia	et al.				_			
		AC 6,486,057 B1			11-2002	Yel	n et al.		<u></u>					
		AD 6,465,372 B1			10-2002	Xia	et al.		 		-			
		AE 6,444,593 B1			09-2002	Ngo	et al.	,			_			
		AF 6,436,808 B1			08-2002	· Ngo	) +.		·- <u>-</u> -		-			
		AG 6,435,943 B1			08-2002	Cha	ang +.							
		A	н	6,429,115 B1	08-2002	Tsa	ıi +.				/			
		Al 6,284,677 B1			09-2001	Hsiao +.								
<u></u>			77	6,030,901	02-2000	Hop	oper +.	er +.			_			
_	. AK			6,133,618	10-2000	Ste	iner				-			
<u> </u>		<del></del>	_		FOR	EIGN P	ATENT DOCUME	ENTS						
	• 1 1			ocument lumber	Date		Country		Class	Su	bcl s		lation	
	3	AN	0	942330	9/99	EPO					_	Yes	No	
[7		AO	6	-244172	09/94	Japan					_	Х		
6		AP	2	00068261A	03-2000	Japan							-	
				OTHER REFE	RENCES (i	ncluding	Author, Title, Da	ate, Pertinent P	ages, Etc	.)				
	Q AR Beekman , K. et al., "Sub-Micro ULSI Conf, Portland, OR,Oct. 19						n Gap Fill and 995, pp. 1-7.	In-Situ Planari	sation Us	ing I	Flowfil	ll™"Techi	nology",	
	AS Kiermasz, A. et al., "Planarisatio Conf., California, Feb. 1995, pp.						on for Sub-Micro 1-2.	n Devices Util	ising a N	ew (	Chemi	istry", DU	MIC	
(	<b>}</b>	AT		Ralls, K. et al Inc., pp. 312-3	., "Introduc 313.	tion to	Materials Science	ce and Engine	ering", 19	76 J	ohn \	Wiley & S	Sons,	
EX	AMINE	R	··· ··	· · · · · · · · · · · · · · · · · · ·			DATE CONSID	SIDERED B/73/OS						
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				U	ENT DOCUMEN	тѕ							
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۵		AA	5,994,217	11-1999	Ng			_					
		АВ	5,991,217	11-1999	Tavrov	Tavrow et al.				-	_		
		AC	5,985,519	11-1999	Kakan	u et al.	t al.			-			
		AD	5,747,388	05-1998	Kūsters et al.								
		AE	5,639,687	06-1997	Romai	n et al.			F	-			
		AF	5,498,555	03-1996	Lin		_				-		
		AG	6,498,084B2	12-2002	Bergei	nont			-	-			
		АН	5,036,383	07-1991	07-1991 Mori							<del></del>	
		Al	6,638,875	10-2003	Han e	t al.						ı	
		AJ	6,720,247	04-2004	Kirkpa	tricktl et al.				•			
		AK	6,723,631	04-2004	Noguc	hi et al.		_		_			
		AL	5,593,741	01-1997	Ikeda								
				FC	OREIGN P	ATENT DOCUMEN	ITS						
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	$\bot$	_	Number				····		88		Yes	No	
<u>A</u>		<u>АМ</u>	0 471185 A2	02/92	EPO	•							
<u>C</u>		AN	0 464515 A3	01/92	EPO	·	↓ <u> </u>						
3		AO	0 771886 A1	05/97	EPO					•			
0		AP_	08-213386A	08-1996	Japan		-						
			OTHER	REFERENCES	S (includin	g Author, Title, Dat	e, Pertinent Page	es, Etc.)					
C	А	R	Wolf, "Silicor	Processing	for the	VLSI Era, Vol.	2: Process	Integration,	. ©	1990	, pp. 189	-190.	
C.	A	AS Wolf et al., "Silicon Processing for the VLSI Era - Vol. 1 - Process Technology," Prologue, page xxiii (2 pages total).								е,			
٠ و٠	. A	ιT	Heavens, O.	S., "Optical	Propertie	s of Thin Solid	Films", pp.	48-49.			-		
EXAMINI	ER	Q				DATE CONSIDERED 8/13/05							
*EXAMIN	*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.												

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0		AA	6,121,133	09-200	0 1	lyer et al.				_			
		AB	2002/0016085	02-200	2 F	luang et al.		·	$\overline{+}$				
		AC	2003/0164354	09-200	3 F	fsieh et al.				_			
		AD	2003/0173671	09-200	3 F	lironaga et al.,		_	-				
		AE	2004/0175933	09-200	4 S	Shishida et al.			-				
		AF	2004/0126671	07-200	4 S	Smith et al.			-	-			
	AG 6,348			. 02-200	2 G	Supta et al.		-	-	-			
	AH 6,790,778		09-200	4 C	Cheng et al.								
	Al 6,632,712B1 10-20		10-200	3 A	ang et al.			•					
		AJ	5,711,987	01-199	01-1998 Bearinger et al.								
		_		F	OREIGN	PATENT DOCUMEN	ITS						
			cument mber	Date		Country		Class	Sul cla			lation	
4	AM	0	588087 A2/3	03-1994	EPO			_			Yes .	No	
<u>a</u>	AN	9	055351	02-1997	JP								
<u>O</u> :	AO	42	9473A	04-2001	TW								
<u>(</u>	AP	42	0844A	02-2001	TW						,		
<u></u>	AQ	36	8687A	09-1999	TW				_				
			OTHER F	REFERENCE	S (includ	ing Author, Title, Date	e, Pertinent Page	s, Etc.)					
٥	AR	. :	Jenkins, F. et	al., "Fund	amenta	als of Optics", Pro	operties of Li	ght, pp. 9-	10.				
a	AS		Dammel, R.R. Back Condition	et al., "Dens, SPIE V	epende /ol. 304	nce of Optical Co 49 (1997), pp. 96	onstants of A 3-973.	Z® BARLi	M Bo	ottom	Coating	on	
9	TA		Bencher, C. e Technology (M	t al., "Diele larch 1997	ectric A	Antireflective Coat 109-114.	ings for DŲV	Lithograp	hy",	Solid	State		
<u></u>	AU		Grant, J., "Ha	ckh's Chen	nical D	ictionary", McGrav	w-Hill, Inc. 19	69, Fourth	Edi	ition,	page 27.		
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0	AK	0	778496 A2	05/96	EPO					_		
a	AL	06	067019A	03/94	JP (abstract)			<u> </u>				
<u>C</u>	AM	11	172845 A2 01-2002 EPO					_	二			
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			OTHER REF	ERENCES (i	including	Author, Title, D	ate, Pertinent P	ages, Etc	.)			
Anonymous, "New Gas Helps Make Faster ICs", Mai 1999, p. 118.								ign, Vol.	71,	lss. 2	1, Nov. 4	4,·
9	AP		McKenzie, D.I 82, pp. 326-3		New Tec	hnology for PA	CVD", Surface	and Coa	tings	Tecl	nnology,	Vol.
0	AQ		Shibata, N., Antireflective pp. 997-1001.	Coating for	emical V Solar C	apor-Deposited ells", Jap. Jour	Silicon Oxide/ c. of App. Phys	Silicon O: sics, Vol.	xynit 30,	ride D No. 5	ouble-La 5, May 19	yer 991,
	AR			,		-	•					
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